IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Thomas A. Figura et al.

Title:

USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE FORMATION OF A

SEMICONDUCTOR DEVICE

Docket No.:

303.932US4

Serial No.: 09/471,460

Filed:

December 22, 1999

Due Date: September 27, 2006

Examiner:

Calvin Lee

Group Art Unit: 2818

MS AF

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

We are transmitting herewith the following attached items (as indicated with an "X"):

X Amendment and Response Under 37 CFR 1.116 (10 pgs.).

X Communication Concerning Related Applications (1 pg.).

If not provided for in a separate paper filed herewith, Please consider this a PETITION FOR EXTENSION OF TIME for sufficient number of months to enter these papers and please charge any additional fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

Customer Number 21186

Atty: Timothy B. Chise

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CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being filed using the USPTO's electronic filing system EFS-Web, and is addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this 25 day of September, 2006.

Name

Signature

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

(GENERAL)

S/N 09/471,460 PATENT

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Applicant: Thomas A. Figura et al. Examiner: Calvin Lee Serial No.: 09/471,460 Group Art Unit: 2818

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Title: USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE

FORMATION OF A SEMICONDUCTOR DEVICE

COMMUNICATION CONCERNING RELATED APPLICATION(S)

MS Amendment

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Applicants would like to bring to the Examiner's attention the following related application(s) in the above-identified patent application:

Serial/Patent No.	Filing Date/Issue Date	Attorney Docket	<u>Title</u>
09470650	December 22, 1999	303.932US5	USE OF A PLASMA SOURCE TO FORM
6716769			A LAYER DURING THE FORMATION
			OF A SEMICONDUCTOR DEVICE
09470651	December 22, 1999	303.932US6	USE OF A PLASMA SOURCE TO FORM
			A LAYER DURING THE FORMATION
			OF A SEMICONDUCTOR DEVICE

Continuations and divisionals may be later filed on the cases listed above, or cited to the Examiner in any previous Communication Concerning Related Applications. Applicants request that the Examiner review all continuations and divisionals of the above-listed or previously-cited patent applications before allowing the claims of the present patent application.

Respectfully submitted, THOMAS A. FIGURA ET AL. By Applicants' Representatives,

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